

ABSTRACT

The transparent conductive film 1 includes laminated transparent conductive thin films 10 and 20 of at least two layers. The transparent conductive thin film of the uppermost layer is an amorphous oxide thin film composed of gallium, indium, and oxygen, a gallium content ranges from 49.1 atom % to 65 atom % with respect to all metallic atoms, a work function is 5.1 eV or more, and a surface resistance is $100 \Omega / \square$ or less. The transparent conductive base material includes a transparent substrate and the transparent conductive film 1 formed one or both surfaces of the transparent substrate.